

Dustin Austin

List of Publications by Year in descending order

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8
papers

119
citations

1477746

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1588620

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9
all docs

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docs citations

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202
citing authors

| # | ARTICLE | IF | CITATIONS |
|---|---|-----|-----------|
| 1 | Review "Beyond the Highs and Lows: A Perspective on the Future of Dielectrics Research for Nanoelectronic Devices. ECS Journal of Solid State Science and Technology, 2019, 8, N159-N185. | 0.9 | 17 |
| 2 | Laminate Al ₂ O ₃ /Ta ₂ O ₅ Metal/Insulator/Insulator/Metal (MIIM) Devices for High-Voltage Applications. IEEE Transactions on Electron Devices, 2019, 66, 5260-5265. | 1.6 | 5 |
| 3 | Assessment of Energy Barriers Between ZrCuAlNi Amorphous Metal and Atomic Layer Deposition Insulators Using Internal Photoemission Spectroscopy. Physica Status Solidi - Rapid Research Letters, 2018, 12, 1700437. | 1.2 | 8 |
| 4 | Atomic Layer Deposition of Ruthenium and Ruthenium Oxide Using a Zero-Oxidation State Precursor. Chemistry of Materials, 2017, 29, 1107-1115. | 3.2 | 50 |
| 5 | Effect of Tip Morphology of Vertically Aligned Alumina Nanowire Arrays on Ovalbumin Uptake of Dendritic Cells. Microscopy and Microanalysis, 2017, 23, 1292-1293. | 0.2 | 0 |
| 6 | Electrode modulated capacitance-electric field nonlinearity in metal-insulator-metal capacitors. Applied Physics Letters, 2017, 110, 263503. | 1.5 | 10 |
| 7 | Plasma Enhanced Atomic Layer Deposition of Al ₂ O ₃ /SiO ₂ MIM Capacitors. IEEE Electron Device Letters, 2015, 36, 496-498. | 2.2 | 16 |
| 8 | Atomic layer deposition of bismuth oxide using Bi(OCMe ₂ iPr) ₃ and H ₂ O. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2014, 32, 01A113. | 0.9 | 9 |